Substitute Form PTO-1449 (Modified)  U.S. Department of Commerce Patent and Trademark Office				Attorney's Docket No. Intel 10559-88700 P17697	Intel 10559-887001 /		Application No. 10/649,354	
ln ln	t	n Disclosur Sta by Applicant veral sheets if necess	sa(y)	Applicant Florence Eschbac	Applicant Florence Eschbach et al.			
			Filling Date August 26, 2003	( I mind pam		Group Art Unit Unknown		
		**************************************		nt Documents				
Examiner Initial	Desig. ID	Document Number	Publication Date	Patentee	Class	Subclass	Filing Date If Appropriate	
. ,	AA							
	AB							
	AC							
	AD							
	'AE							
	AF							
	AG							
	AH							

Foreign Patent Documents or Published Foreign Patent Applications							
Examiner Initial	Desig. ID	Document Number	Publication Date	Country or Patent Office	Class	Subclass	lation No
	AI						
	AJ						 
	AK						

	Other Documents (include Author, Title, Date, and Place of Publication)						
Examiner Initial		Desig. ID	Document				
AL / Photomask Japan, 2002		Shu et al.; "Hard Pellicle Study for 157-nm Lithography," Preprint, to appear in the Proceedings of Photomask Japan, 2002					
		AM	Radiation Physics and Chemistry 62 (2001) 39-45; Oshioma et al.; "Chemical structure and physical properties of radiation-induced crosslinking of polytetrafluoroethylene"; www.elsevier.com/locate/radphyschem; © 2001 Elsevier Science Ltd.				
		AN	Reu et al.; "Mechanical analysis of hard pellicles for 157 nm lithography"; to appear in the Proceedings of the 2001 SPIE Symposium on Optical Microlithography XIV, Vol. 4346, 2001;				
		AO	Kozeki et al.; "Longevity of 193nm/ArF Excimer Pellicle"; April 26, 2001; Mitsui Chemicals, Inc., Pellicles Dept.				
1		ΑP	D.W. Van Krevelen, with collaboration of P.J. Hoftyzer; "Properties of Polymers, Their Estimation and Correlation with Chemical Structure," Second, completely revised edition, pp. 68-73; Elsevier Scientific Publishing Company, Amsterdam-Oxford-New York 1976				

Examiner Signature	Date Considered 6/20/05				
EXAMINER: Initials citation considered. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.					
	Substitute Disclosure Form (PTO-1449)				